IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

re patent application of

Guy Moshe Cohen

Serial No.: 10/645,646

Group Art Unit: Not Yet Assigned

Filing Date: August 22, 2003

Examiner: Unknown

For:

STRAINED-CHANNEL FIN FIELD EFFECT TRANSISTOR (FET) WITH A

UNIFORM CHANNEL THICKNESS AND SEPARATE GATES

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Sir:

Under the provisions of 37 CFR §1.97 through §1.99 and pursuant to applicant's duty of disclosure under 37 CFR §1.56, applicant respectfully brings the following documents listed on the attached form PTO-1449, to the attention of the Examiner in charge of the above-identified application. Copies of the listed documents are provided herewith for the convenience of the Examiner.

This citation does not constitute an admission that the references are relevant or material to the claims. They are only cited as constituting related art of which the applicant is aware.

It is respectfully requested that the listed references be considered by the Examiner and formally made of record in this application.

Please charge any deficiencies in fees and credit any overpayment of fees to Assignee's Deposit Account No. 50-0510.

Respectfully submitted,

Sean M. McGinn

Registration No. 34,386

	<u>م</u>		e u	Docket Number (Optional) YOR920030328US1		Application Number 10/645,646					
R	Diro:	RMATION DISCLOSURE Alse several sheets if necessary	CITATION		Applicant(s) Guy Moshe Cohen						
ONFORMATION DISCLOSURE CITATION (See Several sheets if necessary) (NOV)					Filing Date August 22, 2003		Group Art Unit Not Yet Assigned				
17/	٠.	TRADERARY		U.S. PAT	ENT DOCUMENTS						
*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE		NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE			
		6,413,802 B1	07/02/02	Hu et a	1.	-					
72		6,593,625 B2	07/15/03	Christi	ansen et al.	·					
 -	7										
								,			
:	*	*	-		•						
							·				
					-4			-34-			
					4						
								*			
-				FOREIC	GN PATENT DOCUMENTS		. 6	*			
	REF	DOCUMENT NUMBER	DATE		COUNTRY	CLASS	SUBCLASS	Translation YES NO			
	·										
-	1						·				
				,							

,	 			-							
- 4							Date, Pertinent Pa				
					Spacer FinFET: nanoscale 2002.		•				
		K. Rim, J.L. Hoyt, J.F. Electron Devices, 47(7).	Gibbons, "Fabi , p. 1406-1415.	rication a	nd Analysis of Deep Submi	cron Strain	ed-Si N-MOSFI	ET's", IEEE Trans.			
EXAMINI	ER				DATE CONSIDERED	<u> </u>					

Form PTO-A820 (also form PTO-1449)

considered. Include copy of this form with next communication to applicant.

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not

. /	I.P.	MARION STORES	« CITATION	YOR920030328		10/645,646			
/O	infor	MATION DISCLOSURE	TITATION	Applicant(s) Guy Moshe Cohen					
וחוו	ro, _N	mu -		Filing Date August 22, 200		roup Art Unit Not Yet	t Assigned	1	
\(\(\frac{1}{2}\)		are state of	υ	J.S. PATENT DOCUMENTS					
EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING IF APPROI		
			1				RU		
				~					
	\square		+-+		1				
	\vdash		++	<u> </u>		<u> </u>			
			+ +						
			+	· · · · · · · · · · · · · · · · · · ·	· ·				
			+		-				
			+			 	 		
	\vdash		-		-				
	-					· -			
					1	* .			
			•	· · · · · · · · · · · · · · · · · · ·	1	<u> </u>	<u></u>		
	,		1	FOREIGN PATENT DOCUMENTS		1		lation	
	REF	DOCUMENT NUMBER	DATE .	COUNTRY	CLASS	SUBCLASS	YES	NO NO	
•				•	* .				
k				<u>-</u> ,				·	
						,			
				×					
					Author, Title, Do				
	T	P.M. Mooney, "Strain Review Journal, Conti	Relaxation and Dis inuation of Material	locations in SiGe/Si Structures", ls Science Reports, Volume R17,	, Materials Sci No. 3, pp. 105-	ence & Engina 146, (1996).	eering, RR	eports: A	
<u></u>	_							<u> </u>	
	<u> </u>								
,			<u>V</u> .					<u>-</u>	
EXAMINER				DATE CONSIDERED			· -		
EXAMINE	R: Initia	l if citation considered, whether	or not citation is in con	nformance with MPEP Section 609; Di	raw line through	citation if not in	conformanc	e and not	
considered	. Includ	e copy of this form with next com	umunication to applicar	nt.					